



FIG. 1

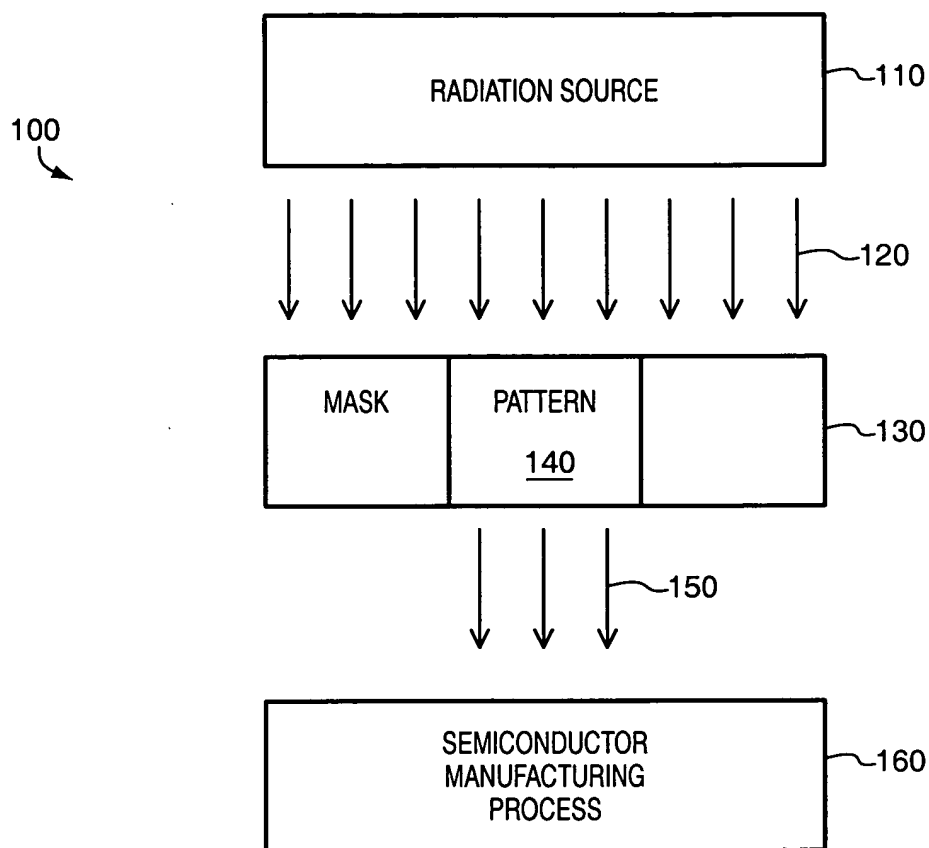
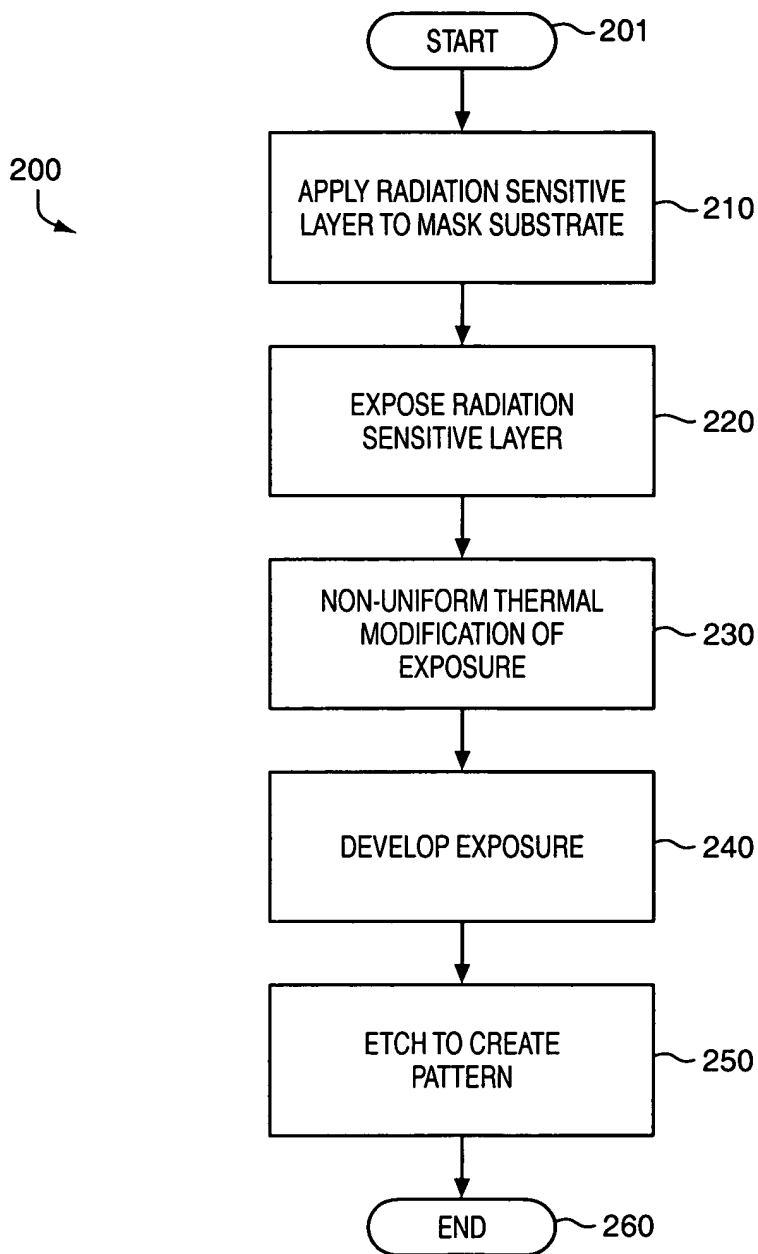




FIG. 2



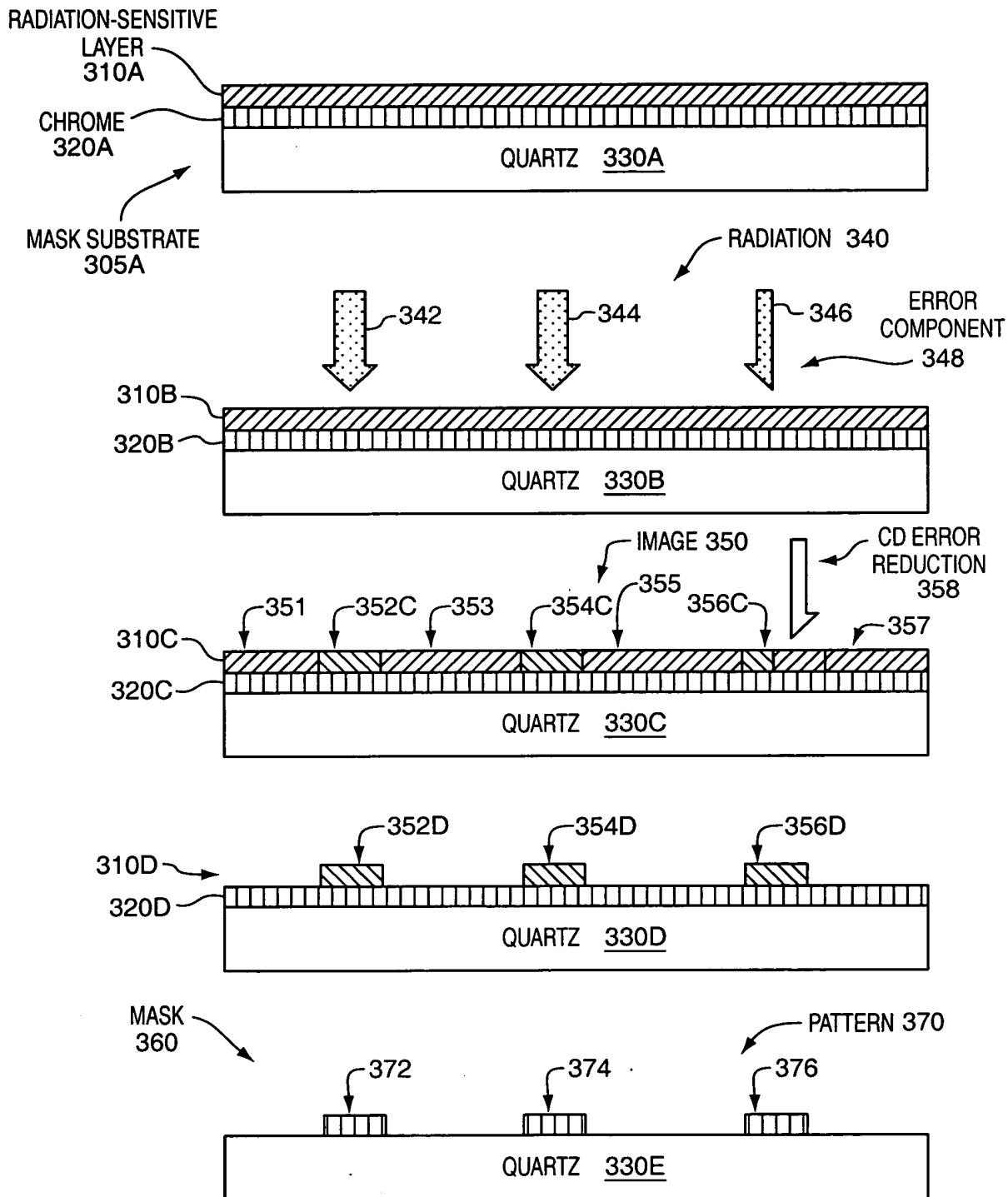


FIG. 3

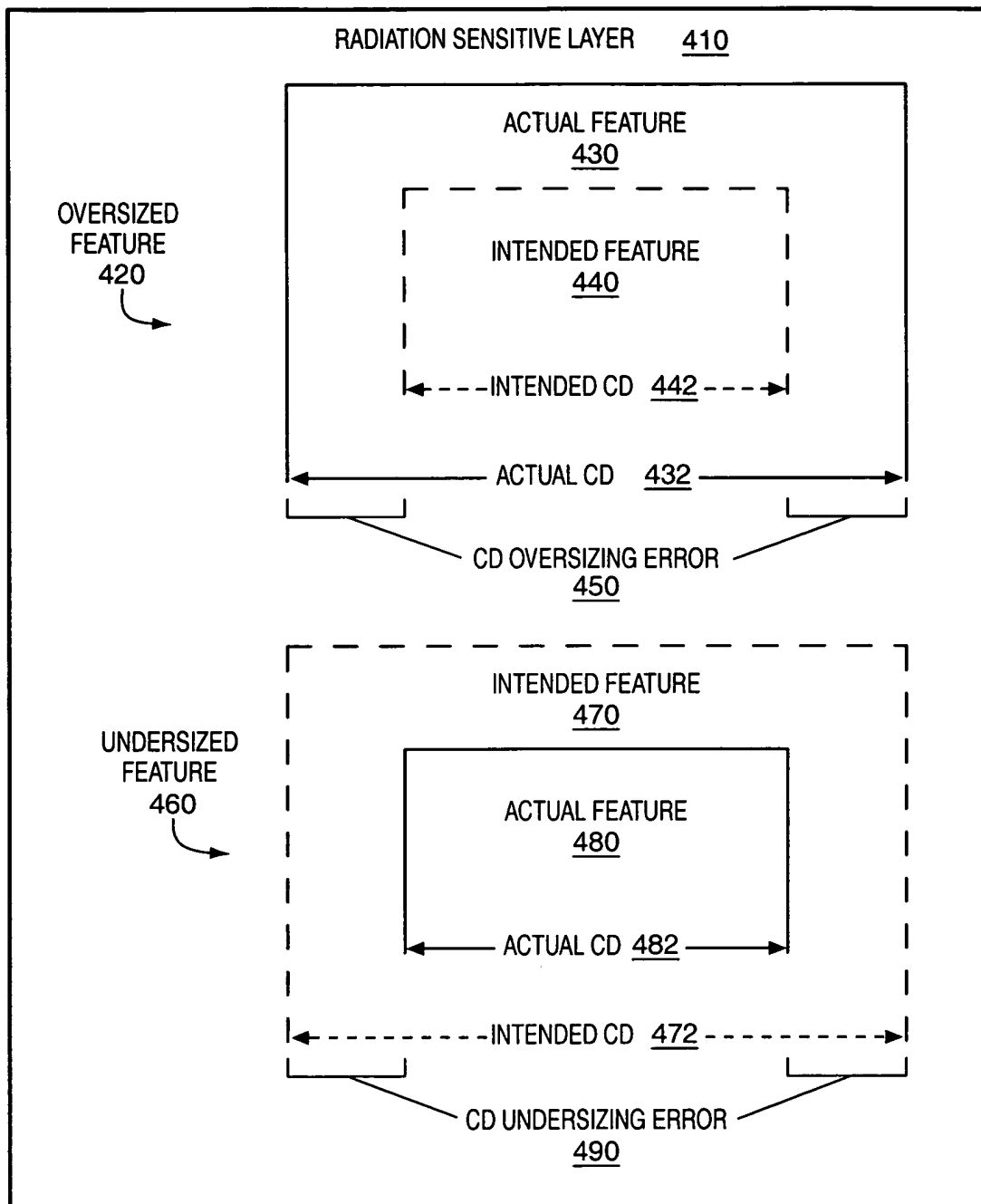


FIG. 4



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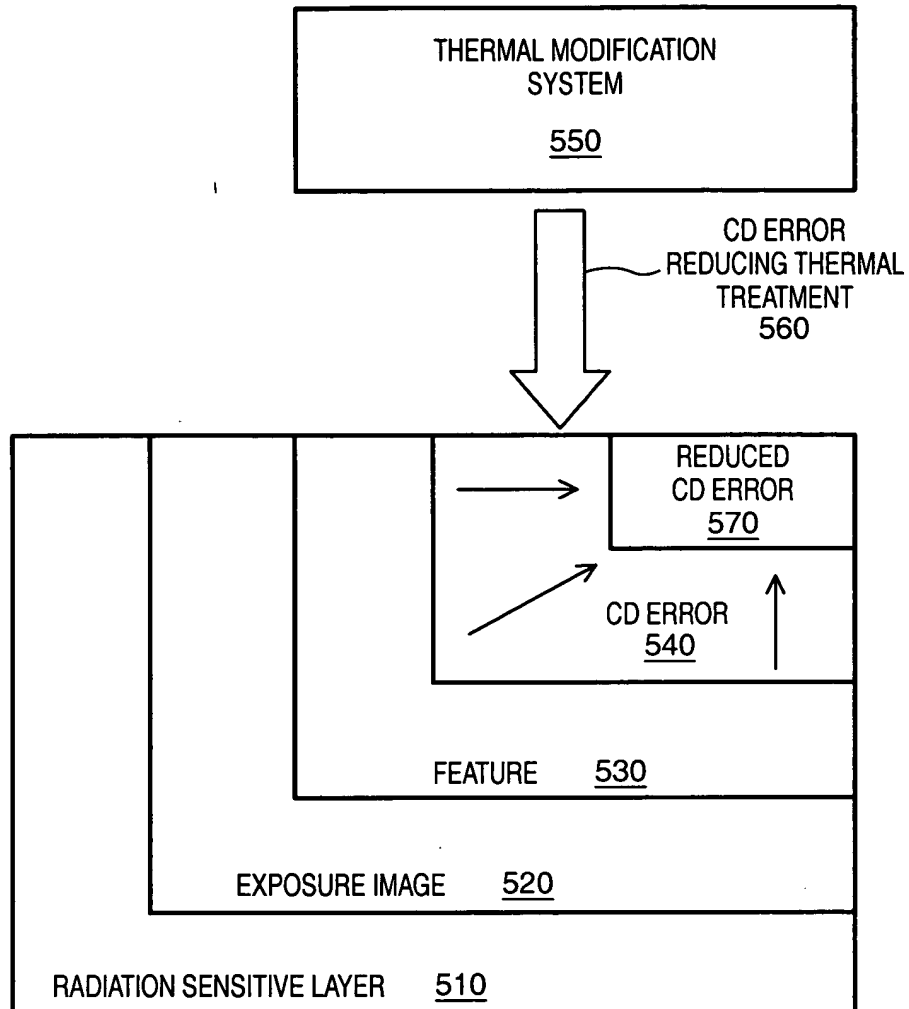


FIG. 5

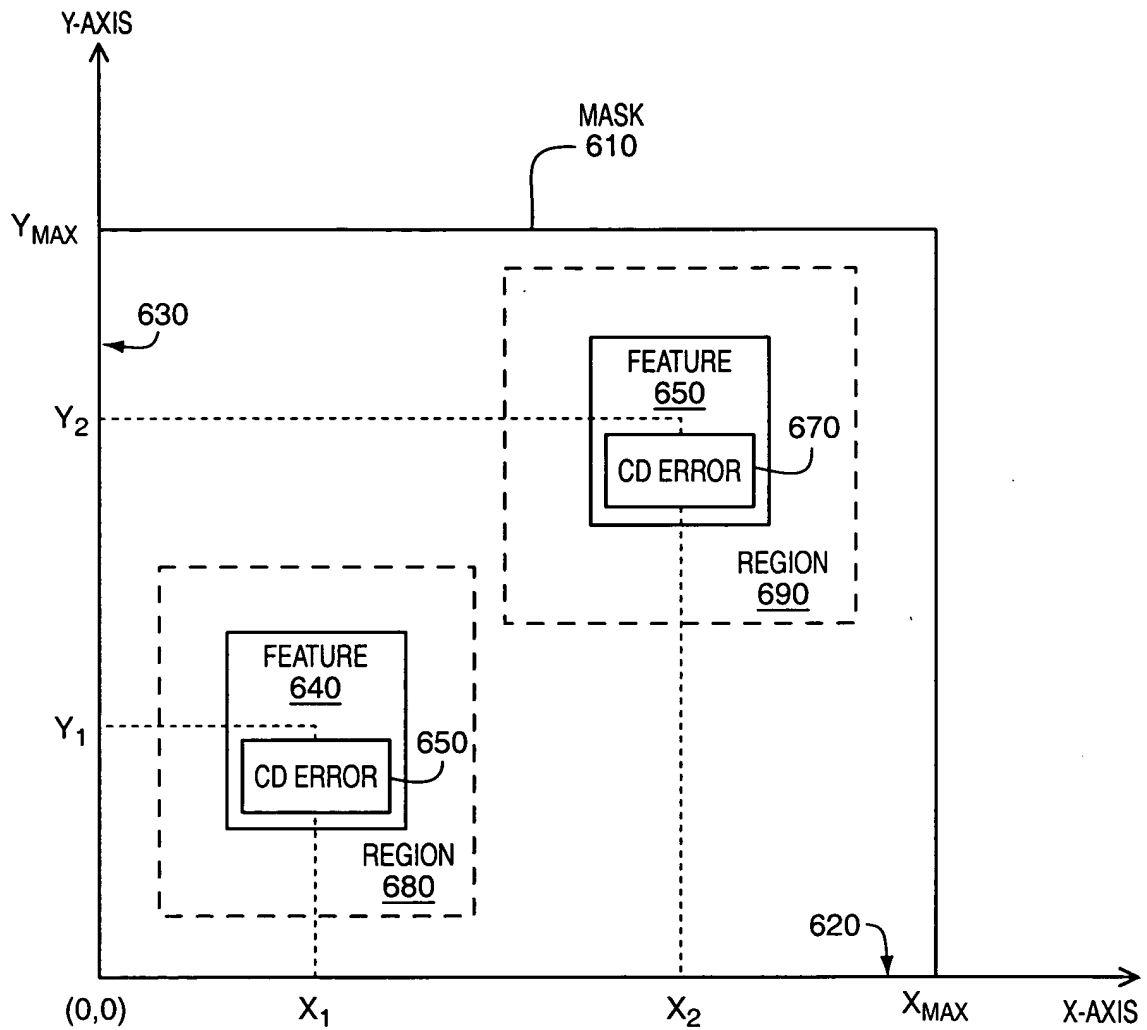
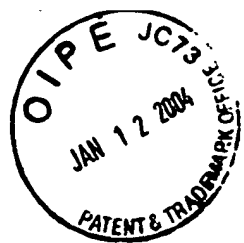


FIG. 6



Title: "Post Exposure Modification of Critical Dimensions In Mask Fabrication"
Inventors: Takeshi et al. Application No.: 09/965,280 Attorney Docket No.: 42P11370
Blakely, Sokoloff, Taylor & Zafman 303-740-1980

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THERMAL MODIFICATION
SYSTEM
700

LEFT HAND
SIDE 720

RIGHT HAND
SIDE 740

	FIRST CD ERROR <u>730</u>	RADIATION SENSITIVE LAYER <u>740</u>	SECOND CD ERROR <u>750</u>	
THERMAL ENERGY TRANSPORT MEDIUM <u>760</u>				
VARIABLE THERMAL INPUT SYSTEM <u>770</u>				

FIG. 7

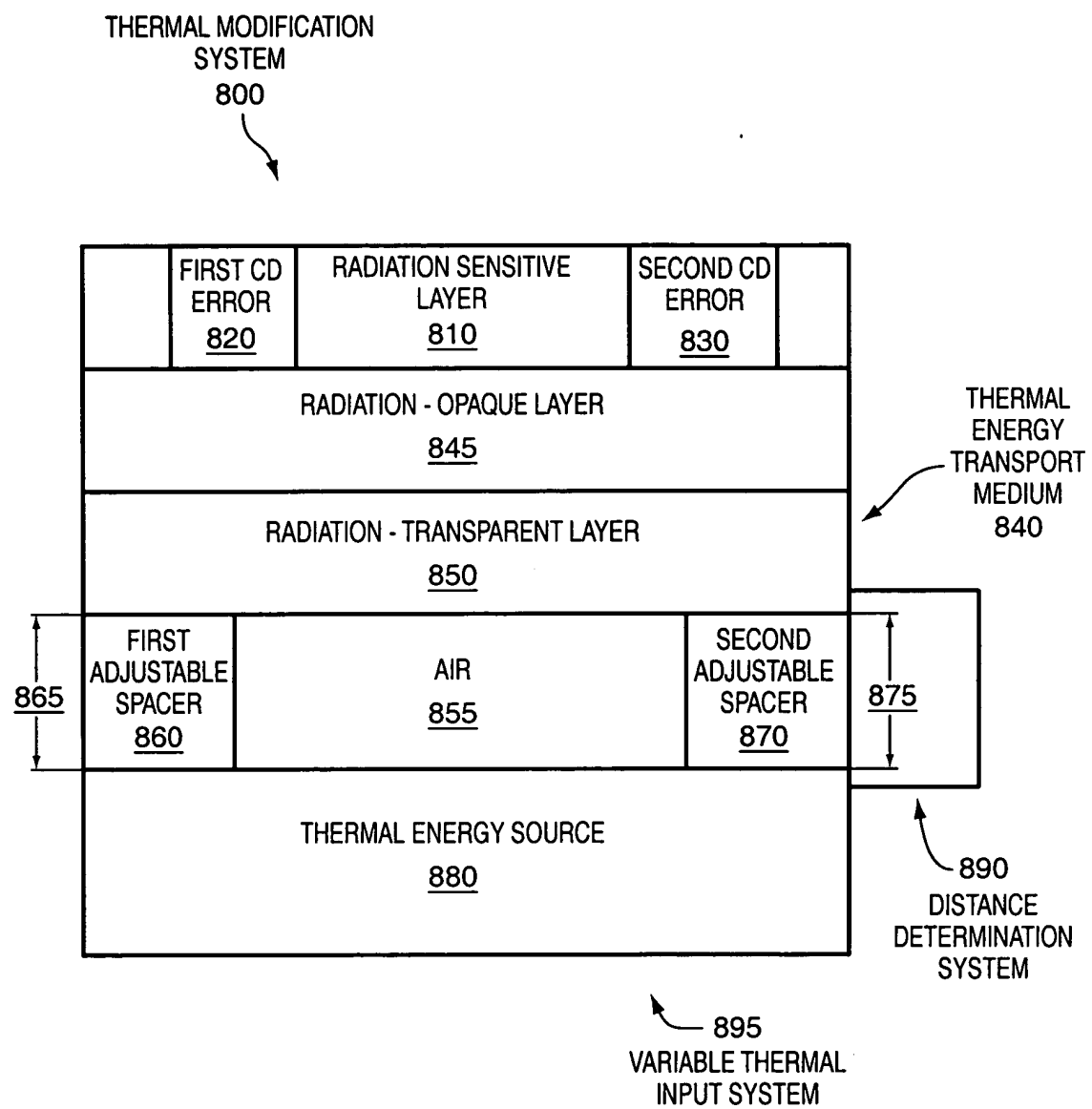
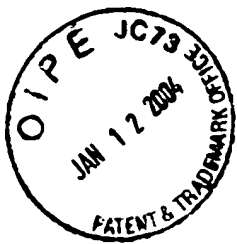


FIG. 8



Title: "Post Exposure Modification of Critical Dimensions In Mask Fabrication"
Inventors: Takeshi et al. Application No.: 09/965,280 Attorney Docket No.: 42P11370
Blakely, Sokoloff, Taylor & Zafman 303-740-1980

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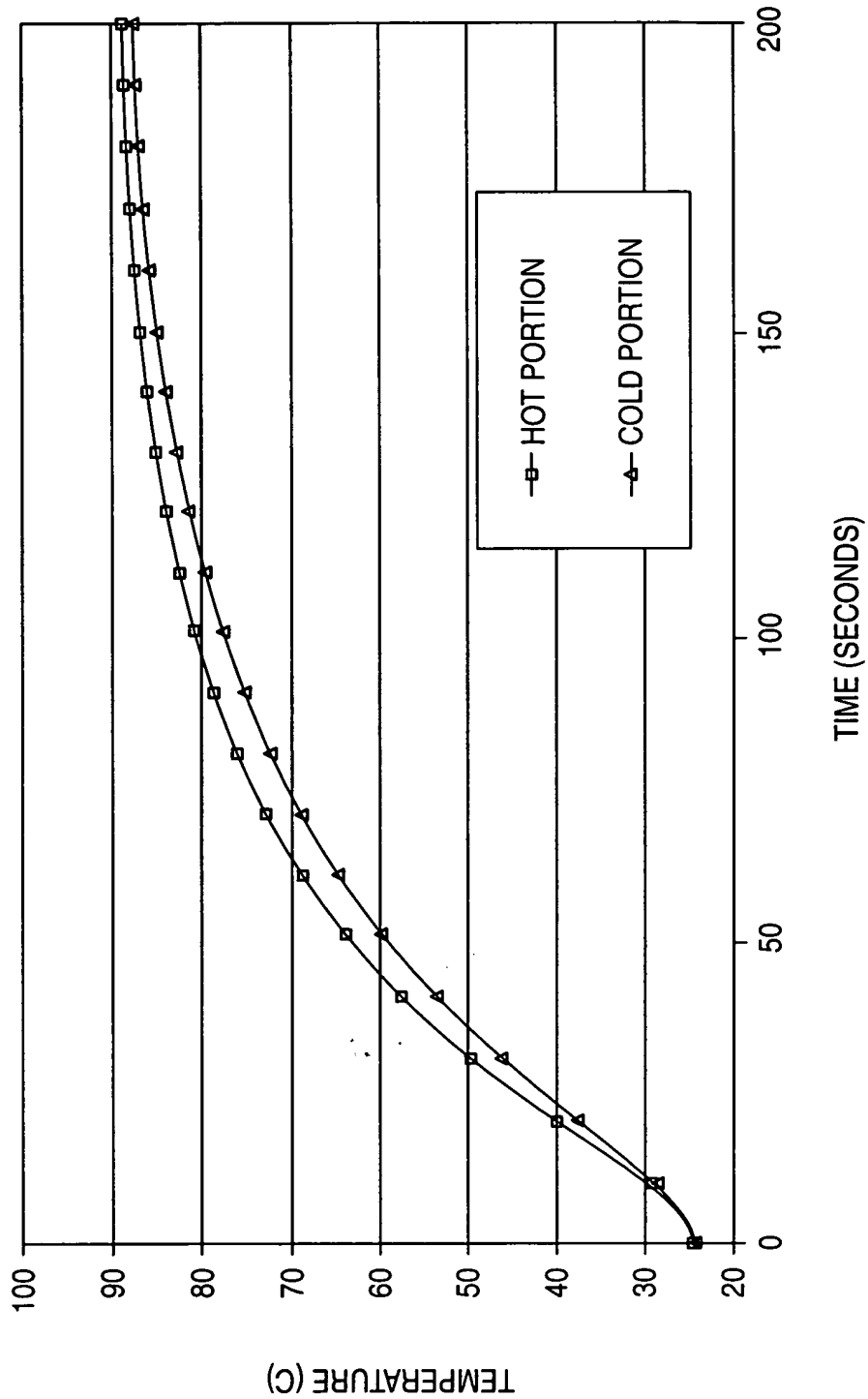
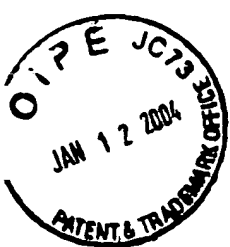


FIG. 9



Title: "Post Exposure Modification of Critical Dimensions In Mask Fabrication"
Inventors: Takeshi et al. Application No.: 09/965,280 Attorney Docket No.: 42P11370
Blakely, Sokoloff, Taylor & Zafman 303-740-1980

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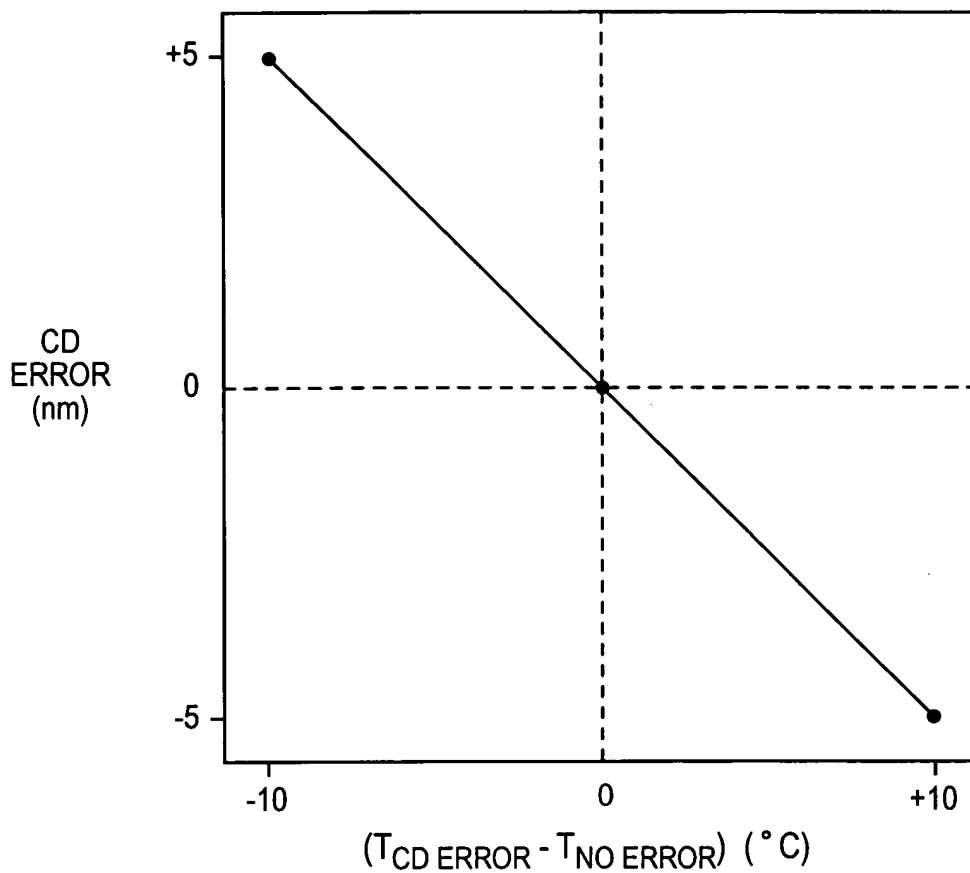


FIG. 10



Title: "Post Exposure Modification of Critical Dimensions In Mask Fabrication"
Inventors: Takeshi et al. Application No.: 09/965,280 Attorney Docket No.: 42P11370
Blakely, Sokoloff, Taylor & Zafman 303-740-1980

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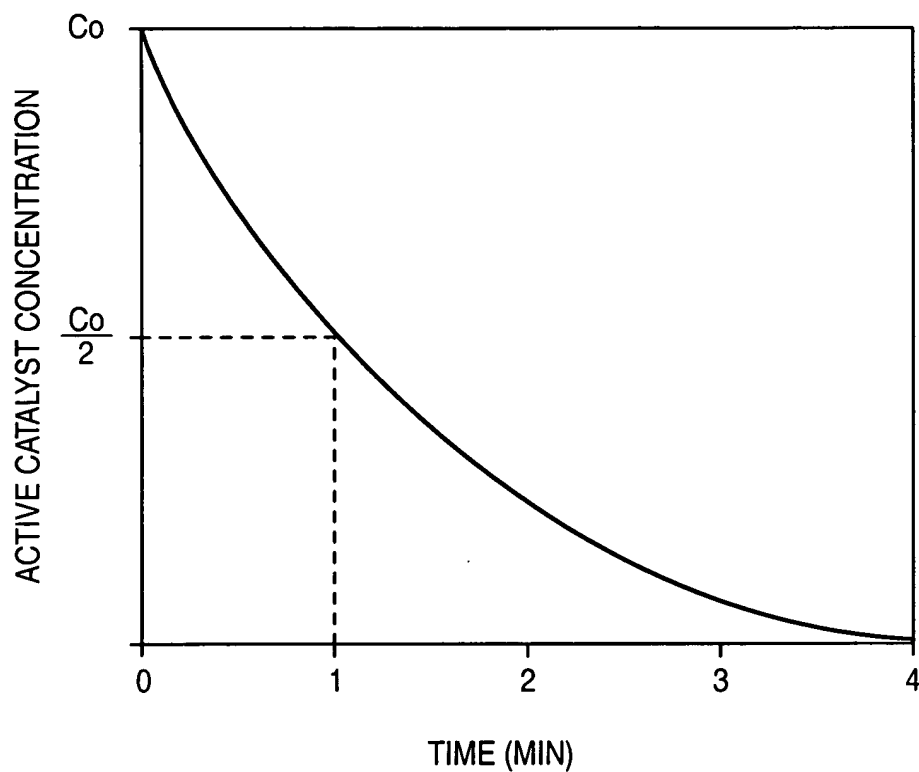


FIG. 11



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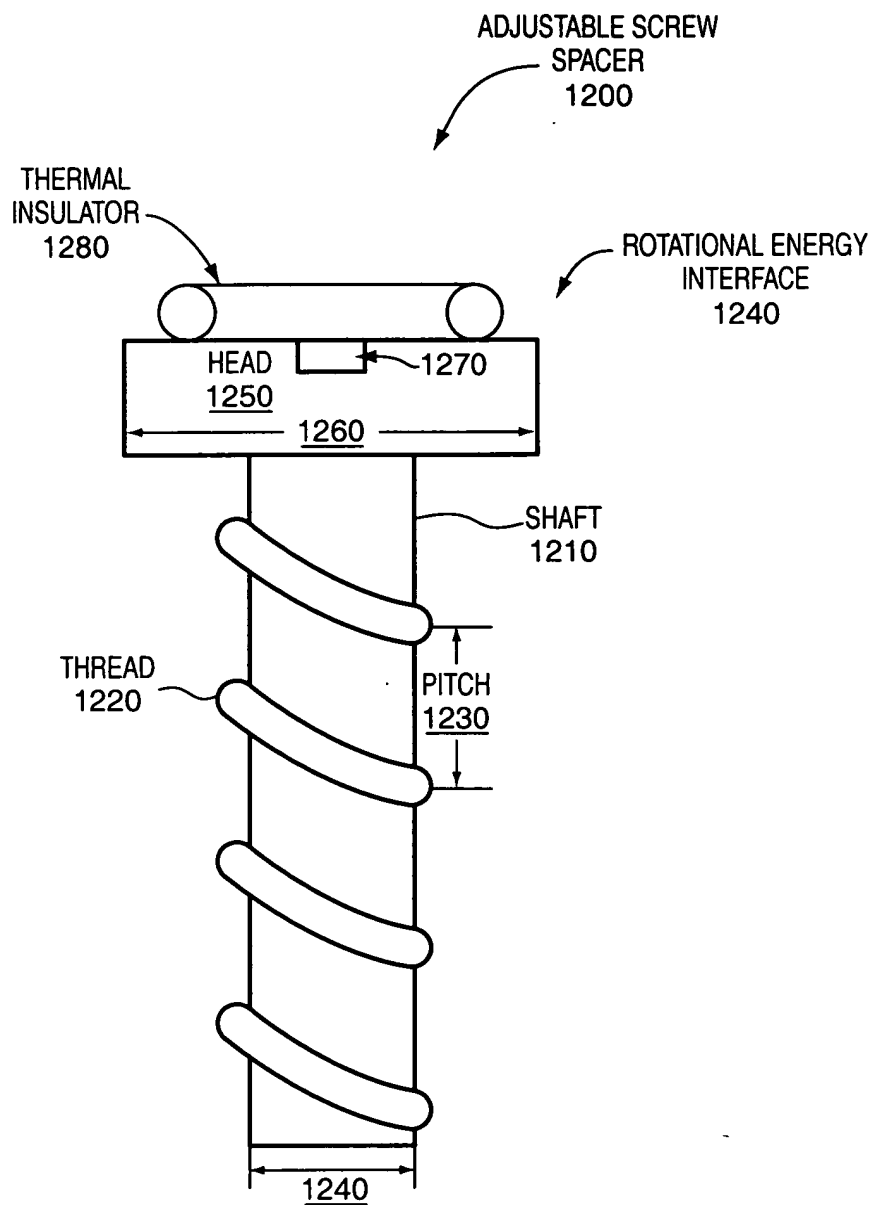


FIG. 12

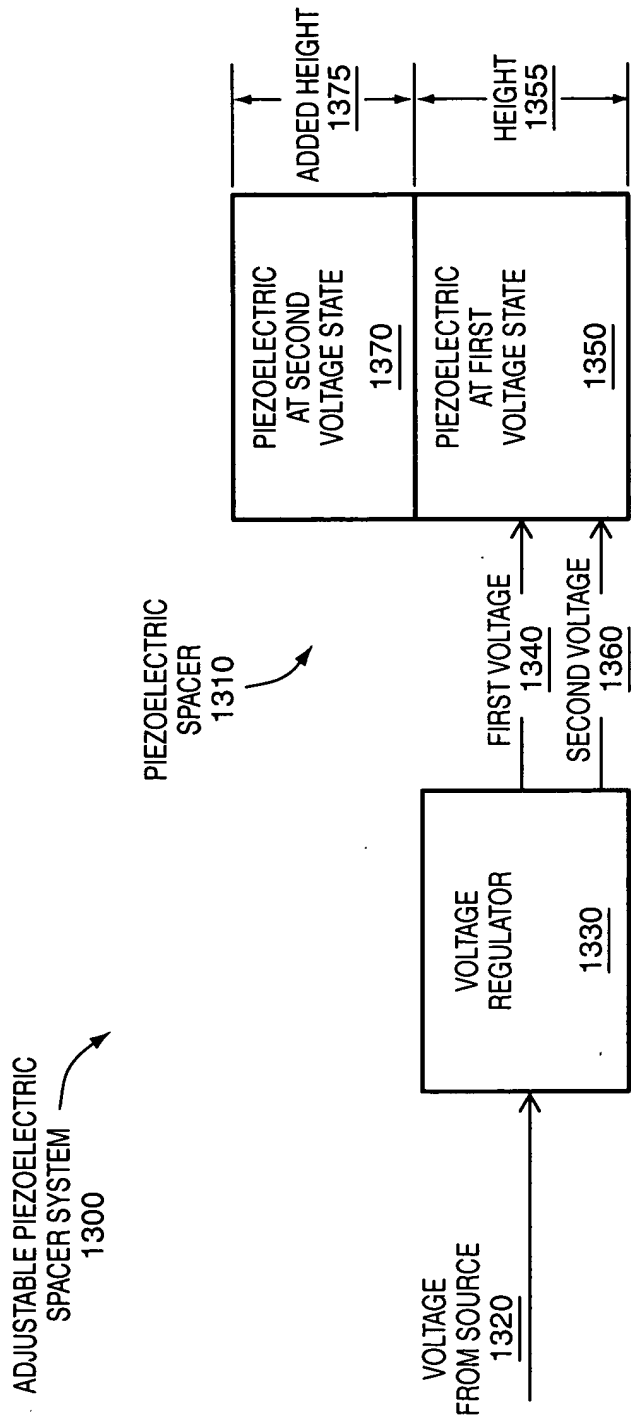
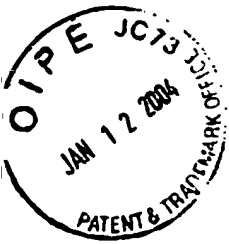


FIG. 13

